

DETAILED ACTION

Notice to Applicant

1. Applicant's Amendment and Response to the Office Action mailed on October 26, 2007 has been entered and made of record.

Response to Amendment

2. In view of applicant's amendments and arguments filed on February 22, 2008, the rejections of claims 1, 3-4, 8-9, 12-14, 17-19 and 41 under 35 U.S.C. 102(b) or 103(a) as stated in the indicated Office Action have been withdrawn.

Examiner's Amendment

3. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

- In claim 2, line 8, substitute "oxidising" with --oxidizing-- before "atmosphere."
- Incorporate Cross-Reference to Related Application in the specification after title "Metallization" and before "Field of the Invention" as follows:

--Cross-Reference to Related application

This application is 371 of PCT/GB03/02613, filed June 18, 2003 which claims the benefit of United Kingdom Patent Application No. 0213925.1, filed June 18, 2002. The disclosures of the above applications are incorporated herein by reference--.

Reason for Allowance

4. Claims 2, 5-7 and 42-46 are allowed.

The following is an examiner's statement of reasons for allowance: claim 2 recites c) reducing the irradiated photosensitive organometallic compound to form metal deposits adhered to the substrate in a process which comprises: 1) a first heating and cooling stage; 2) a second heating and cooling stage in an oxidizing atmosphere; 3) flowing an inert gas over the substrate; and 4) a third heating and cooling stage wherein a reducing gas flows over the substrate to form metal deposits.

Claim 43 recites a) depositing a photosensitive organometallic compound corresponding to formula (I) as described below wherein: M is a member of the group consisting of platinum, palladium, copper, rhodium, tungsten, iridium, silver, gold and tantalum; A is any of oxygen, sulphur, an amide grouping, an amine grouping or an ester grouping; x is 0 or 1; R is a fluoroorgano group; and L is a bidentate ligand.

Claim 44 recites a) depositing a photosensitive organometallic compound selected from group consisting of: bis-(perfluoropropyl)-1,5-cyclooctadiene platinum (II); bis-(perfluoropropyl)-1-methyl-1,5-cyclooctadiene platinum (II); and bis-(perfluoropropyl)-1-fluoromethyl-1,5-cyclooctadiene platinum (II) onto a substrate.

Claim 45 recites c) reducing the irradiated photosensitive organometallic compound to form metal deposits adhered to the substrate by a process comprising: steps (1), (2), (3) and (4) as stated in the claim.

Claim 46 recites c) reducing the irradiated photosensitive organometallic compound to form metal deposits adhered to the substrate by a process comprising: steps 1), 2), 3) and 4) as stated in the claim.

These features in combination with the other elements of the claims are neither disclosed nor suggested by the prior art of record.

Claims 5-7 and 42 depend from claim 2, so they are allowed for the same reason.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to CHEUNG LEE whose telephone number is (571)272-5977. The examiner can normally be reached on Monday through Friday from 8:30AM to 5:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, please contact the examiner's acting supervisors, Scott Geyer 571-272-1958 and Walter Lindsay, Jr.

571-272-1674. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Cheung Lee/
Examiner, Art Unit 2812
April 7, 2008

/Scott B. Geyer/
Acting SPE of Art Unit 2812